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Docket No.: M4065.0139/P139-A

(PATENT)

5/29/03

Shm H

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Cem Basceri

Application No.: 09/633,132

Filed: August 4, 2000

For: METHOD FOR IMPROVING THE
SIDEWALL STOICHIOMETRY OF THIN
FILM CAPACITORS

Confirmation No.:

Group Art Unit: 2815

Examiner: E. Lee

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MAY 27 2003
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AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action dated February 24, 2003, please amend the above-identified U.S. patent application as follows:

In the Claims

Please cancel claims 47 and 56. Please replace claims 39, 41-46, 48, 50-55, and

74 with amended claims 39, 41-46, 48, 50-55, and 74 as follows:

39. (Fifth Amended) A capacitor comprising:

a material layer having a first level and a second level, said first and second levels being connected by at least two sidewall regions between said first and second levels; and